

FIG. 1 is a cross-sectional view of a device 100. The device 100 includes a substrate 102, a first layer 104, a second layer 106, and a third layer 108. A central region 110 is defined by a first side wall 114a and a second side wall 114b. A top layer 116 is disposed on the substrate 102. A bottom layer 118 is disposed on the substrate 102. A first gap 106a is formed between the first layer 104 and the second layer 106. A second gap 108 is formed between the second layer 106 and the third layer 108. A first distance D1 is defined between the top layer 116 and the first layer 104. A second distance D2 is defined between the second layer 106 and the third layer 108.

FIG. 1

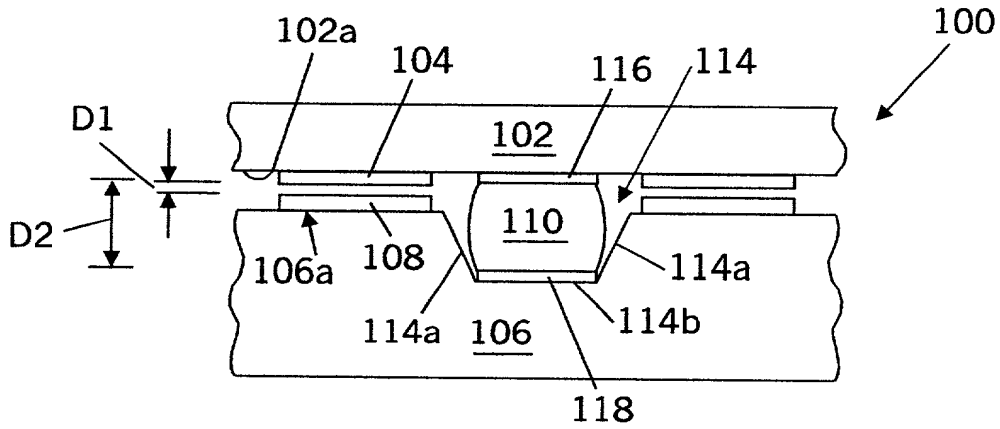


FIG. 2

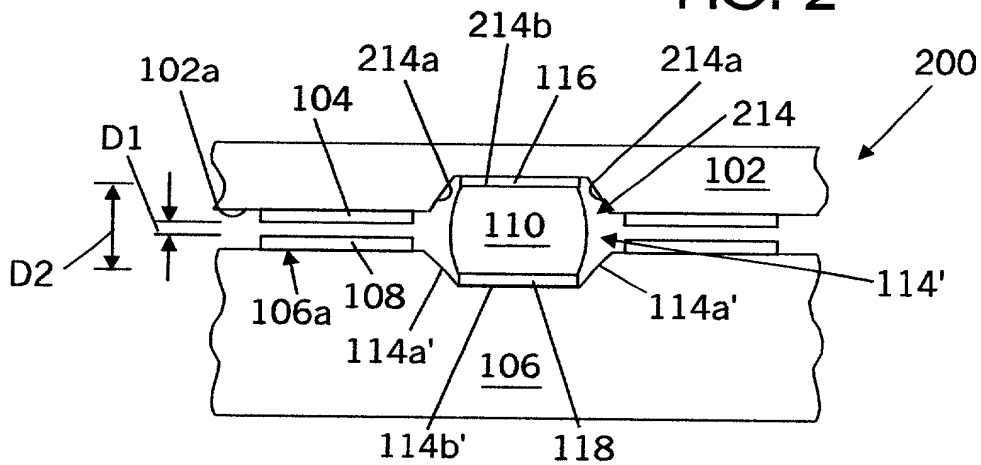


FIG. 3

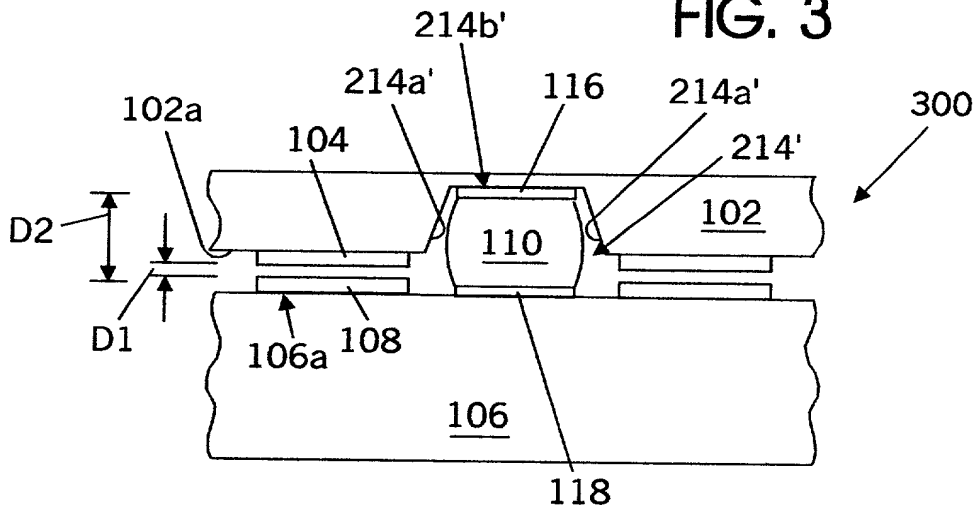


FIG. 4

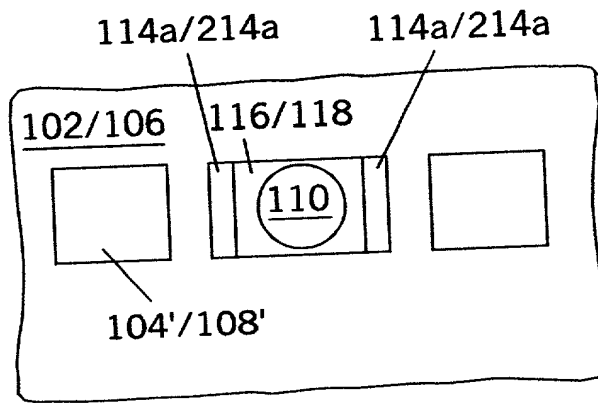


FIG. 5

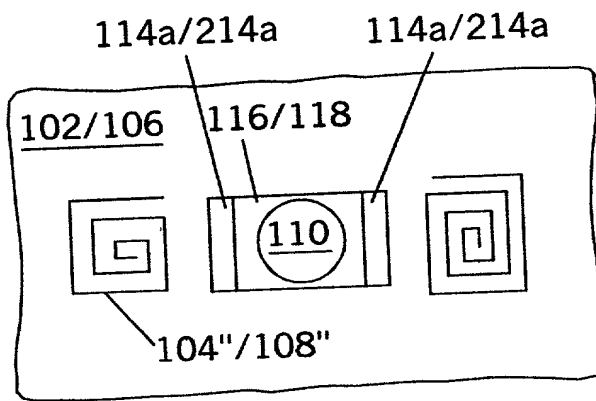
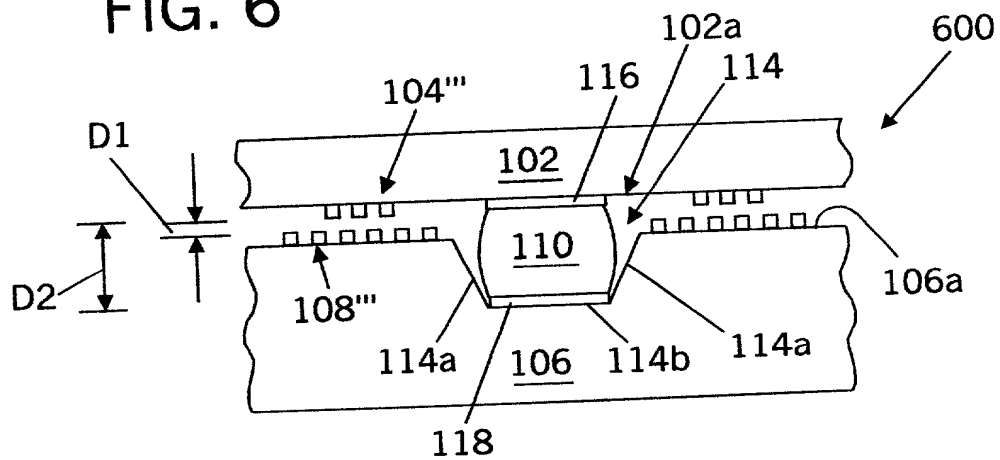


FIG. 6



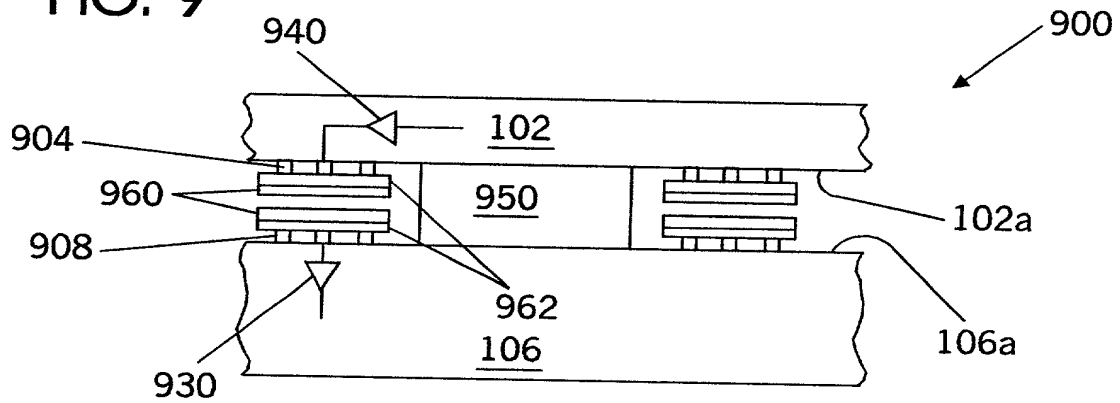
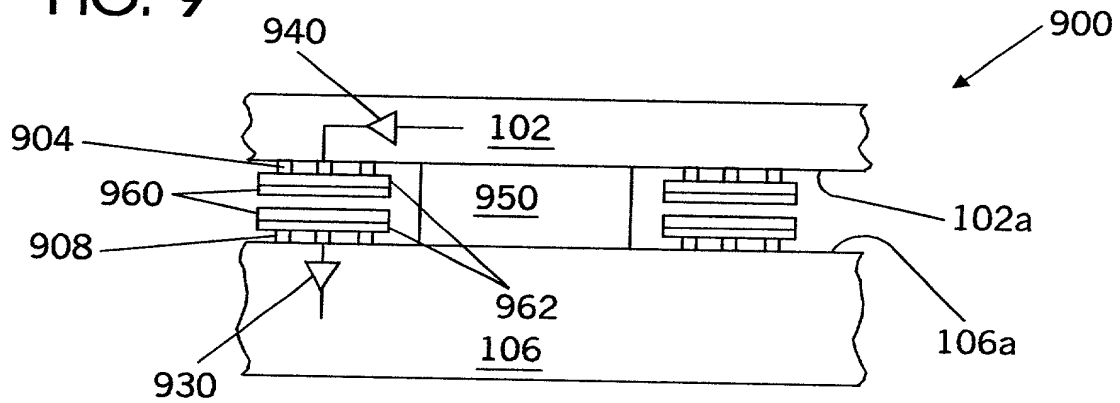
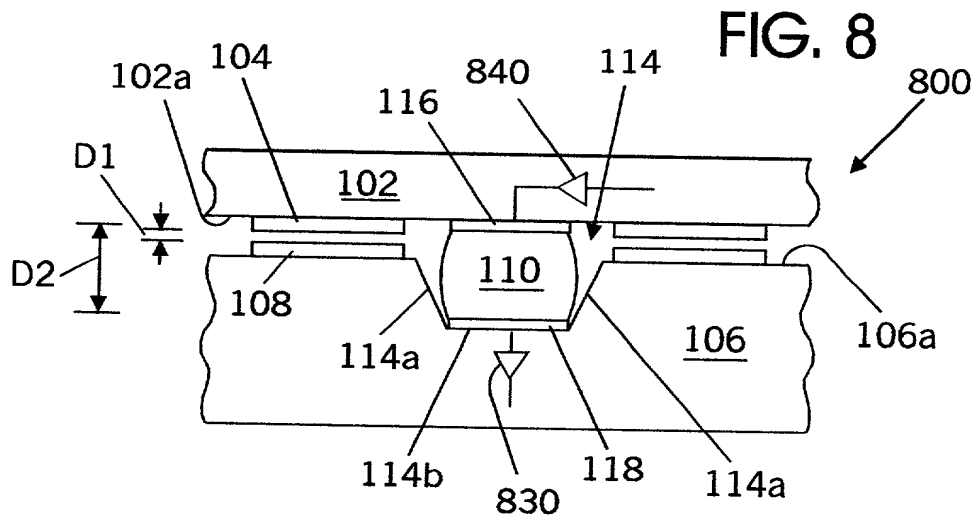
[illegible]

FIG. 10

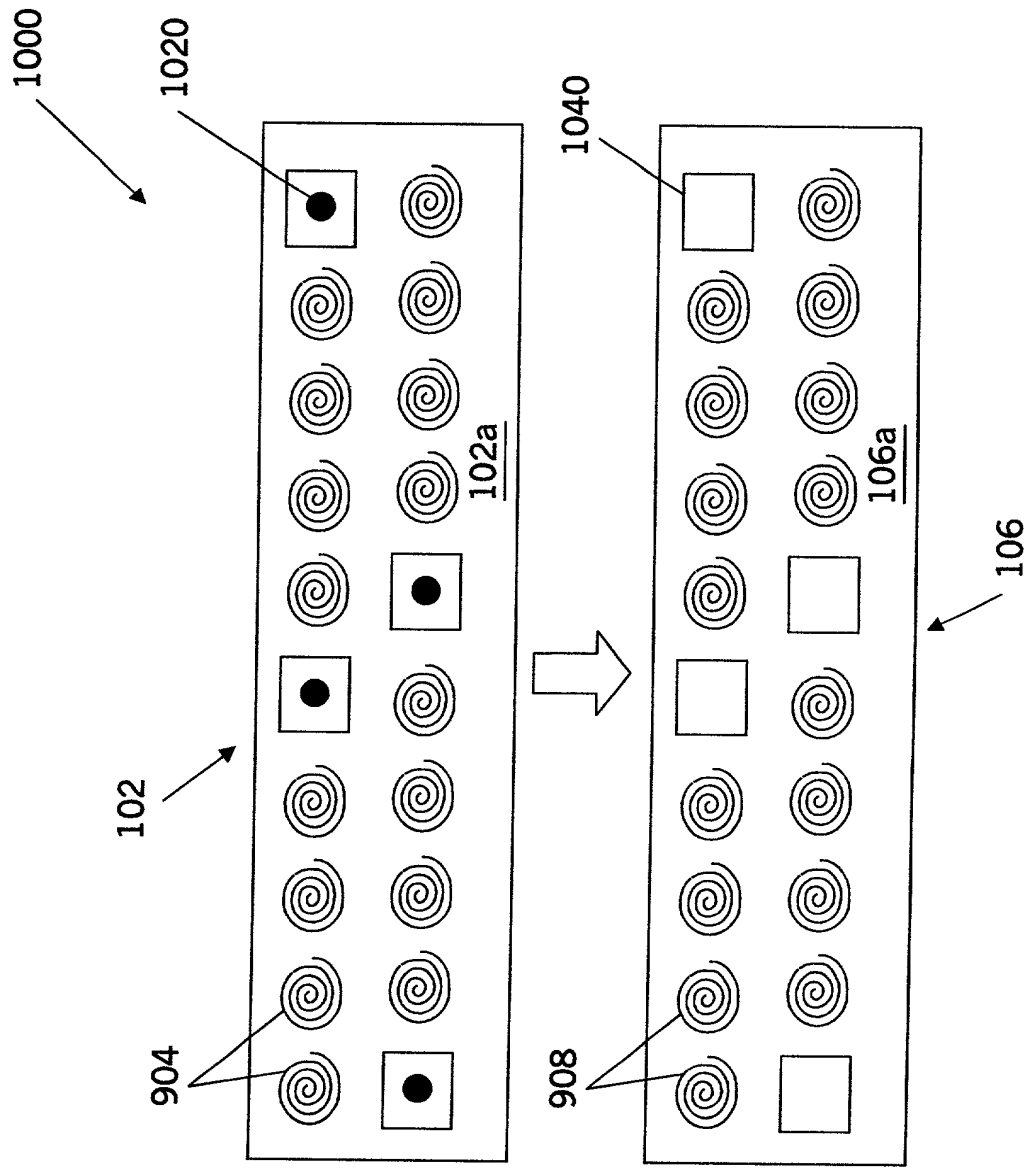


FIG. 11

